

ABSTRACT OF THE DISCLOSURE

An exposure apparatus exposes a transfer pattern of a mask onto a photosensitive substrate in an overlapping manner. The exposure apparatus comprises an illumination optical system for guiding illumination light to the mask. An imaging optical system in the illumination optical system forms an illumination area on the mask. The exposure apparatus comprises a lens driving apparatus. The lens driving apparatus moves at least one of lenses constituting the imaging optical system along the optical axis and so forth, thereby correcting an optical characteristic of the imaging optical system.